

In re: Kong et al.
Serial No.: 09/715,576
Filed: November 17, 2000
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AMENDMENTS TO THE CLAIMS

1-21 (Cancelled)

22. (Currently Amended) A chemical vapor deposition system according to Claim 49
21 wherein said reaction vessel is made of quartz.

23. (Cancelled)

24. (Currently Amended) A chemical vapor deposition system according to Claim 49
21 wherein said source of electromagnetic radiation comprises an induction coil surrounding
said reaction vessel.

25-48 (Cancelled)

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49. (New) A chemical vapor deposition system consisting essentially of:
a reactor vessel formed of a material substantially transparent to electromagnetic
radiation;
a gas supply system in fluid communication with said reactor vessel;
a source of electromagnetic radiation external to said reaction vessel; and
a susceptor within said reaction vessel, and formed of a material that is thermally
responsive to electromagnetic radiation, said susceptor being an inverted truncated cone
defined by a plurality of adjacent straight sidewall sections and a plurality of wafer pockets on
the inner circumference of said truncated cone, with the spacing between facing walls being
small enough for said facing walls to heat the exposed face of a facing substrate wafer to
substantially the same temperature as said susceptor portion heats a substrate wafer that is in
one of said wafer pockets to thereby minimize or substantially eliminate radial and axial
temperature gradients across a substrate wafer.

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50. (New) A chemical vapor deposition system according to Claim 49 wherein said
susceptor is formed from graphite coated with silicon carbide.

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